

| Ref # | Hits | Search Query | DBs | Default Operator | Plurals | Time Stamp |
|-------|------|---|----------------------------|------------------|---------|------------------|
| L2 | 4 | ((rie etch\$6) with (low adj temperature)) with ((below less) near (zero degree celsius)) | US-PGPUB; USPAT | OR | ON | 2004/12/06 09:50 |
| L3 | 271 | 438/978.ccls. | US-PGPUB; USPAT | OR | OFF | 2004/12/06 09:53 |
| L4 | 70 | (semiconductor wafer silicon substrate) and (pattern\$4 resist photoresist lithograph\$7 photolithograph\$7) and ((hole open\$4 aperture) same (taper\$3 isotropic\$6 slant\$4 angl\$4) same mask\$4 same ((organic flare silk polyimide) with (dielectric insulat\$4))) | US-PGPUB; USPAT | OR | ON | 2004/12/06 09:53 |
| L5 | 18 | ("4745086" "4994404" "5405791" "5670401" "5719089" "5801077" "5861343" "5866448" "5989966" "6022782" "6103563" "6103588" "6153455" "6156598" "6214655" "6265253" "6294480" "6495430").PN. | US-PGPUB; USPAT; USOCR | OR | OFF | 2004/12/06 10:37 |
| L6 | 150 | (438/620.ccls. 438/637.ccls. 438/640.ccls. 438/669.ccls. 438/671.ccls. 438/673.ccls. 438/780.ccls.) and ((semiconductor wafer silicon substrate) and (pattern\$4 resist photoresist lithograph\$7 photolithograph\$7) and ((hole open\$4 aperture) same (taper\$3 isotropic\$6 slant\$4 angl\$4) same mask\$4 same (organic flare silk polyimide dielectric insulat\$4))) | US-PGPUB; USPAT | OR | ON | 2004/12/06 10:41 |
| L7 | 80 | (pattern\$4 resist photoresist lithograph\$7 photolithograph\$7) and ((hole open\$4 aperture) with (taper\$3 isotropic\$6 slant\$4 angl\$4)) and mask\$4 and (organic flare silk polyimide) | EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/12/06 11:10 |
| L8 | 10 | (dual adj hard adj mask) with organic | US-PGPUB; USPAT | OR | ON | 2004/12/06 11:18 |
| L9 | 82 | dual adj hard adj mask | US-PGPUB; USPAT | OR | ON | 2004/12/06 11:22 |
| L10 | 13 | "5981913".URPN. | USPAT | OR | OFF | 2004/12/06 11:28 |
| L11 | 0 | "6649517".URPN. | USPAT | OR | OFF | 2004/12/06 11:30 |

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| L12 | 4106 | 438/620.ccls. 438/637.ccls. 438/640.ccls. 438/669.ccls. 438/671.ccls. 438/673.ccls. 438/780.ccls. | US-PGPUB; USPAT | OR | ON | 2004/12/06 11:31 |
| L13 | 885 | (438/620.ccls. 438/637.ccls. 438/640.ccls. 438/669.ccls. 438/671.ccls. 438/673.ccls. 438/780.ccls.) and (hole open\$4 aperture) and (taper\$3 isotropic\$6 slant\$4 ang\$4) and (mask\$4 resist photoresist) | US-PGPUB; USPAT | OR | ON | 2004/12/06 11:32 |
| L14 | 0 | ("6743712").URPN. | USPAT | OR | OFF | 2004/12/06 11:46 |
| L15 | 5 | ("5913148" "6191028" "6387798" "6503829" "6518174").PN. | US-PGPUB; USPAT; USOCR | OR | OFF | 2004/12/06 11:46 |